

FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)				ATTY DOCKET NO. 03500.102994.		APPLICATION NO. 10/530,549	
				APPLICANT KAZUHIKO FUKUTANI ET AL.			
				FILING DATE January 30, 2006		GROUP 1743	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	2005/0053773 A1	03/10/05	Fukutani et al.	428	209		
	2004/0043208 A1	03/04/04	Fukutani et al.	428	304.4		
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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT	
	JP 2001-261376	09/26/01	Japan			Abstract	
	JP 9-157062	06/17/97	Japan			Abstract and English Translation	
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
	C.D. Adams et al., "Monte Carlo Simulation of Phase Separation During Thin-Film Codeposition," J. Appl. Phys. 74 (3), 1 August 1993, American Institute of Physics, pp. 1707-1715.						
	C.D. Adams et al., "Transition from Lateral to Transverse Phase Separation During Film Co-deposition," Appl. Phys. Lett. 59 (20), 11 November 1991, American Institute of Physics, pp. 2535-2537.						
	C.D. Adams et al., "Phase Separation During Co-deposition of Al-Ge Thin Films," J. Mater. Res., Vol. 7, No. 3, March 1992, Materials Research Society, pp. 653-667						
	M. Atzmon et al., "Phase Separation During Film Growth," J. Appl. Phys. 42 (2), 15 July 1992, American Institute of Physics, pp. 442-446.						
	M. Jacobs et al., "Unbalanced Magnetron Sputtered Si-Al Coatings: Plasma Conditions and Film Properties Versus Sample Bias Voltage," Surface and Coatings Technology 116-119 (1999) pp. 736-741.						
EXAMINER				DATE CONSIDERED 7/5/2007			

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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